

Docket No.: 50432-485



PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of

Wen-Jie QI, et al.

Serial No.: 10/023,328

Group Art Unit: 1765

Filed: December 20, 2001

Examiner: Lan Vinh

For: NITRIDE OFFSET SPACER TO MINIMIZE SILICON RECESS BY USING POLY
REOXIDATION LAYER AS ETCH STOP LAYER

#4

11463
me

REQUEST FOR APPROVAL OF DRAWING AMENDMENT

Mail Stop
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

RECEIVED
MAY 13 2003
TC 1700

Sir:

Approval of the changes made to Figure 6A, as shown in red ink on the attached photocopies, is courteously solicited.

Respectfully submitted,

MCDERMOTT, WILL & EMERY

John A. Hankins
Registration No. 32,029

600 13th Street, N.W.
Washington, DC 20005-3096
(202) 756-8000 JAH:cac
Facsimile: (202) 756-8087
Date: May 12, 2003